hereby certify that this conjespondence is being deposited with the United

Attorney Docket No.: 014089-002580US

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TOWNSEND and TOWNSEND and CREW LLP

By: Il Sucono

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

VEERASAMY, VIJAYEN, et al.

Application No.: 10/773,796

Filed: February 6, 2004

For: RECORDING MEDIA HAVING PROTECTIVE OVERCOATS OF HIGHLY TETRAHEDRAL AMORPHOUS CARBON AND METHODS FOR THEIR PRODUCTION

Examiner: PADGETT, Marianne L.

Art Unit: 1762

SUPPLEMENTAL INFORMATION
DISCLOSURE STATEMENT UNDER 37

CFR §1.97 and §1.98

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The references cited on attached form PTO/SB/08A&B are being called to the attention of the Examiner. Copies of the references [in compliance with the requirements of 1287 OG 163] are enclosed.

It is respectfully requested that the cited references be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

09/01/2005 CNGUYEN2 00000018 201430 10773796

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Application No.: 10/773,796

Page 2

As provided for by 37 CFR 1.97(g) and (h), no inference should be made that the information and references cited are prior art merely because they are in this statement and no representation is being made that a search has been conducted or that this statement encompasses all the possible relevant information.

This IDS is being filed before the mailing date of the final Office Action or Notice of Allowance.

Please charge the IDS fee of \$180 to Deposit Account No. 20-1430. Please deduct any additional fees from, or credit any overpayment to, the above-noted Deposit Account.

Respectfully submitted,

Nena Bains Reg. No. 47,400

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Complete if Known					
Application Number 10/773,796					
Filing Date	February 6, 2004				
First Named Inventor	Veerasamy, Vijayen				
Art Unit	1762				
Examiner Name	PADGETT, Marianne L.				
Attorney Docket Number	014089-002580US				

	U.S. PATENT DOCUMENTS+				
		Document Number			
Examiner Initials*	Cite No. ¹	Number Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear

				FOREIGN PA	TENT DOCUME	ENTS		
Examiner	Cite	Foreign Patent Document				Name of Patentee or	Pages, Columns, Lines,	
Initials*	No.1	Country Code ³	Number ⁴	Kind Code ⁵ (if known)	Publication Date MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	T⁰
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		NON PATENT LITERATURE DOCUMENTS	
Examiner Cite Initials * No.		Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	Т :
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Examiner	Date
	Considered

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Substitute	for form 1449	A&B/PTO			Complete if Known
INICO		ON DIC	CL OCUPE	Application Number	10/773,796
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Filing Date	February 6, 2004
			PPLICANT	First Named Inventor	Veerasamy, Vijayen
				Art Unit	1762
(use as mar	y sheets as	necessary)	Examiner Name	PADGETT, Marianne L.
Sheet	2	of	2	Attorney Docket Number	014089-002580US

		NON PATENT LITERATURE DOCUMENTS	
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T 2
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Examiner	 Date	
Signature	Considered	

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